Serial No. 10/567,369 Docket No. PKHF-04053US HIR.201

AMENDMENTS TO THE CLAIMS

Please amend the claims as follow:

- (Currently Amended) A semiconductor layer, comprising:

 a first layer comprising a Ga₂O₃ system single crystal substrate; and
 a second layer comprising an oxidation gallium a nitride surface of said first layer
 containing oxygen and nitrogen.
- 2-3. (Cancelled.)
- 4. (Previously Presented) A semiconductor layer according to claim 1, wherein the first layer comprises Ga_2O_3 , $(In_xGa_{1-x})_2O_3$ where $0 \le x < 1$, $(Al_xGa_{1-x})_2O_3$ where $0 \le x < 1$, $(In_xAl_yGa_{1-x-y})_2O_3$ where $0 \le x < 1$, $0 \le y < 1$, and $0 \le x + y < 1$ as a main constituent.
- 5. (Cancelled.)
- 6. (Currently Amended) A semiconductor layer, comprising:
 - a first layer comprising a Ga₂O₃ system semiconductor;
- a second layer comprising an oxidation gallium a nitride surface of said first layer containing oxygen and nitrogen; and
 - a third layer comprising a GaN system epitaxial layer grown on the second layer.
- 7-8. (Cancelled.)
- 9. (Previously Presented) A semiconductor layer according to claim 1, wherein the first layer consists of a single crystal β -Ga₂O₃.
- 10. (Previously Presented) A semiconductor layer according to claim 9, wherein the single crystal β -Ga₂O₃ has a prismatic shape having a square in cross section, and its axis direction matches a-axis <100> orientation, b-axis <010> orientation, or c-axis <001> orientation.

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11. (Previously Presented) A semiconductor layer according to claim 1, wherein the first layer comprises $(In_xGa_{1-x})_2O_3$ where 0 < x < 1.

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- 12. (Previously Presented) A semiconductor layer according to claim 1, wherein the first layer comprises $(Al_xGa_{1-x})_2O_3$ where 0 < x < 1.
- 13. (Previously Presented) A semiconductor layer according to claim 1, wherein the first layer comprises $(In_xAl_yGa_{1-x-y})_2O_3$ where 0 < x < 1, 0 < y < 1, and 0 < x + y < 1.
- 14. (Cancelled.)
- 15. (Previously Presented) A semiconductor layer according to claim 6, wherein the first layer consists of single crystal β -Ga₂O₃.

16-20. (Cancelled.)

- 21. (Currently Amended) A semiconductor layer, comprising:
 - a first layer comprising a Ga₂O₃ system single crystal substrate; and
- a second layer comprising a Ga_2O_3 <u>nitride surface of said first layer</u> which contains <u>oxygen and</u> nitrogen,

wherein the second layer comprises a GaN system compound semiconductor.